A

| | Application No. | Applicant(s) |
|---|---|---|
| **Notice of Allowability** | 10/785,254 | PANG, LINYONG |
| | Examiner | Art Unit | |
| | Sun J. Lin | 2825 | |

*-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address--*

All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. **THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS.** This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.

1. ☒ This communication is responsive to *Amendments filed on 02/02/2006 and 02/13/2006*.

2. ☒ The allowed claim(s) is/are *1,3,4,6,7,10-12,14-16 and 18-20, renumbered (37 CFR 1.126)*.

3. ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).

    a) ☐ All    b) ☐ Some*    c) ☐ None  of the:

        1. ☐ Certified copies of the priority documents have been received.

        2. ☐ Certified copies of the priority documents have been received in Application No. _____ .

        3. ☐ Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).

    * Certified copies not received: _____ .

Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.
**THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.**

4. ☐ A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.

5. ☐ CORRECTED DRAWINGS ( as "replacement sheets") must be submitted.

    (a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review ( PTO-948) attached

        1) ☐ hereto or 2) ☐ to Paper No./Mail Date _____ .

    (b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of
    Paper No./Mail Date _____ .

    **Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).**

6. ☐ DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.

**Attachment(s)**
1. ☐ Notice of References Cited (PTO-892)
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)
3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/08), Paper No./Mail Date _____
4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material

5. ☐ Notice of Informal Patent Application (PTO-152)
6. ☐ Interview Summary (PTO-413), Paper No./Mail Date _____ .
7. ☐ Examiner's Amendment/Comment
8. ☒ Examiner's Statement of Reasons for Allowance
9. ☐ Other _____ .

### *Reasons for Allowance*

Claims 1, 3, 4, 6, 7, 10 – 12, 14 – 16 and 18 – 20 are allowed over the prior art of record.   An examiner's statement of reasons for allowance is given in the following:

As to Claims 1, 3, 4, 6, 7, 10 – 12, 14 – 16 and 18 – 20, the prior art does not teach or suggest the following subject matters:

- A method of automatically performing a wafer simulation, the method comprising *obtaining threshold data from a look-up table (LUT), which is generated using a model and organized based on feature size, pitch size, and feature/defect identification* in combination with other limitations as recited in independent **Claims 1** and **4**, respectively;

- A method of determining a wafer contour of a mask feature, the method comprising *accessing resist information in a look-up table (LUT) to determine a threshold associated with the mask feature, the LUT is organized based on feature size, pitch size, and feature/defect identification* in combination with other limitations as recited in independent **Claim 7**;

- A computer-implemented program for generating a wafer contour, the program comprising *code for obtaining threshold data from a look-up table (LUT), which is generated using a resist model and organized based on feature size, pitch size, and feature/defect identification* in combination with other limitations as recited in independent **Claim 12**;

- A method of creating a look-up table (LUT) for use in a wafer simulation, the method including *storing thresholds for a plurality of features based on matching in the LUT, which is organized based on feature size, pitch size, and feature/defect identification* in combination with other limitations as recited in independent **Claim 15**.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee.  Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance".
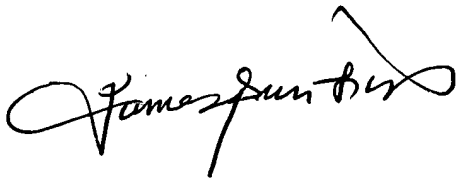
## *Conclusion*

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Sun J. Lin whose telephone number is (571) 272–1899. The examiner can normally be reached on Monday to Friday from 10:00am to 7:00pm.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-1782.

Sun J. Lin
Primary Examiner
Art Unit 2825
March 27, 2006